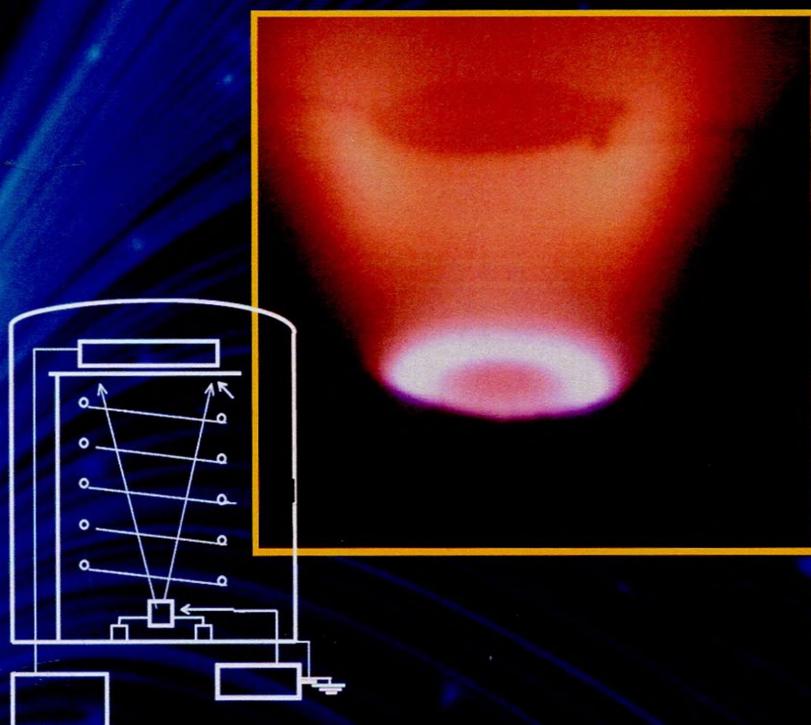


539.23
S 53

THE MECHANISMS OF FORMATION OF THIN FILMS

AND COATINGS DEPOSITED BY PHYSICAL VAPOR DEPOSITION TECHNOLOGY

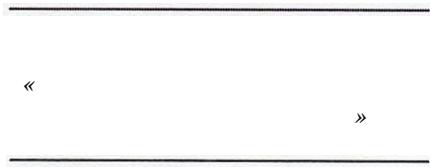
L.R. SHAGINYAN



NATIONAL ACADEMY OF SCIENCES OF UKRAINE
I. N. FRANZEVICH INSTITUTE FOR PROBLEMS
OF MATERIALS SCIENCE

,

■ ■



2017

L. R. SHAGINYAN

THE MECHANISMS OF FORMATION OF THIN FILMS AND COATINGS DEPOSITED BY PHYSICAL VAPOR DEPOSITION TECHNOLOGY

*PROJECT
«UKRAINIAN SCIENTIFIC BOOK
IN A FOREIGN LANGUAGE»*

KYIV
AKADEM PERIODYKA
2017

UDK 539.216
BBK 30.3

S53

Reviewers:

A. I. USTINOV, Dr. Sci., PhD, Professor, Head of the Department
of the Paton Electric Welding Institute of NAS of Ukraine

Yu. N. MAKOGON, Dr. Sci., PhD, Professor of the Department of Physics of Metals,
National Technical University of Ukraine "Kyiv Politechnic Institute"

*Approved for publication by the Scientific Council
of the I. N. Franzovich Institute for Problems of Materials Science
of the National Academy of Sciences of Ukraine
(June 23, 2015, Protocol 6)*

*Publication was funded in the frame of the Targeted Complex
Program “Creation and Development of Scientific Publishing Complex
of the National Academy of Sciences of Ukraine”*

Shaginyan L. R.

S53 The Mechanisms of Formation of Thin Films and Coatings
Deposited by Physical Vapor Deposition Technology / L. R. Shaginyan;
National Academy of Sciences of Ukraine, I. N. Franzovich
Institute for Problems of Materials Science. — Kyiv: Akademperiodyka, 2017. — 174 p.

ISBN 978-966-360-326-1

Explosive development of contemporary plasma based thin film and coating technologies resulted in expanding thin film/coating uses in diverse areas like micro- and optoelectronics, communications and information processing technology, storage and display applications, all kinds of coatings (optical, decorative, environmental and wear resistant), biotechnology, generation and conservation of energy.

Suggesting book is an attempt to fill the gap between great amount of literature devoted to applied and technological problems of films and coatings and the lack of fundamental knowledge about mechanisms of film/coating formation.

**UDK 539.216
BBK 30.3**

© Shaginyan L. R., 2017

ISBN 978-966-360-326-1

© Akademperiodyka, design, 2017

CONTENT

PREFACE	5
CHAPTER 1	
PARTICULARITIES OF FORMATION OF FILMS DEPOSITED BY ION AND REACTIVE ION PLATING	
1.1. Introduction	7
1.2. Principles of film deposition by ion plating.....	8
1.3. Effects producing by high energy particle bombardment on a condensation surface.....	9
1.4. Influence of ion bombardment on earlier stages of the film growth.....	10
1.4.1. Film growth on electrically conductive substrates.....	14
1.4.2. Film growth on electrically non-conductive substrates.....	14
1.5. Influence of energetic bombardment on structure and properties of continuous films	20
1.5.1. Temperature dependent evolution of structure of evaporated films	21
1.5.2. Bombardment-induced changes in structure and related properties of IP-films.....	24
1.6. Particularities of film formation during reactive ion plating.....	34
1.6.1. General approach.....	34
1.6.2. Indium nitride films.....	37
1.6.3. Indium oxide films.....	42
1.6.4. Aluminum nitride films.....	44
1.6.5. Gallium nitride films.....	46
1.7. Physical-chemical model of composition formation during reactive ion plating	50
1.7.1. Role of mutual chemical activity of reacting atoms.....	51
1.7.2. Role of temperature in composition formation.....	53
1.7.3. Role of ion bombardment in film composition formation.....	53
1.8. Epitaxial growth under ion bombardment.....	55
1.8.1. General approach	55
1.8.2. Energy-stimulated epitaxial growth	56
1.9. General remarks.....	68
References	69

Content

CHAPTER 2

**PARTICULARITIES OF FORMATION
OF FILMS DEPOSITED BY SPUTTERING**

2.1. Introduction	72
2.2. Condensation coefficient of sputtered atoms	73
2.3. Surface temperature developing during condensation of sputtered atoms.....	78
2.3.1. Methods and results of surface temperature measurements.....	80
2.3.2. Reasons for the difference between the surface and the substrate temperature.....	84
2.3.3. Model of liquid-like layer.....	85
2.3.4. Surface temperature as an instrument for investigation of the mechanisms of film formation	90
2.3.5. Conclusion.....	95
2.4. Non-uniformity of structure of films deposited by sputtering.....	96
2.4.1. Reasons for structure non-uniformity of magnetron sputtered films.....	96
2.4.2. Film structure model.....	104
2.5. Role of type of film-forming species in formation of composition, structure and properties of sputtered films.....	105
2.6. Particularities of composition formation of alloy and compound films.....	113
2.6.1. Alloy films	113
2.6.2. Compound films	124
2.7. General remarks.....	130
References	131

CHAPTER 3

**PARTICULARITIES OF FORMATION OF FILMS
DEPOSITED BY PULSED LASER EVAPORATION**

3.1. Introduction	134
3.2. Composition of PLD films.....	136
3.2.1. Dependence of the composition of PLD films on processing parameters.....	137
3.2.2. Dependence of the composition of PLD films on the evaporating material.....	140
3.2.3. Mechanisms of formation of low-melting point semiconductor compounds and oxides	140
3.2.4. Mechanisms of formation of refractory materials films.....	141
3.3. Mechanisms of formation of PLD films of selected alloys and compounds [39].....	142
3.3.1. Experimental details.....	142
3.3.2. Alloy evaporation.....	144
3.3.3. Evaporation of compounds with nonvolatile components.....	146
3.3.4. Evaporation of compounds with volatile components.....	147
3.4. Formation of composition of PLD films.....	147
3.4.1. Mechanism of composition formation of alloy films.....	148
3.4.2. Mechanisms of composition formation of compound films.....	148

Content

3.4.3. Composition formation of compound films with volatile component.....	150
3.5. Structure of PLD films.....	152
3.5.1. Role of molecules and larger clusters.....	152
3.5.2. Epitaxial growth of PLD films.....	155
3.6. Macrodefects in PLD films.....	160
3.6.1. Correlation between vapor portion in products of laser-ablated metals and their thermo-physical properties.....	160
3.7. Influence of target characteristics on properties of PLD films.....	164
3.8. General remarks.....	166
References.....	168

24.01.2017. 70×100/16.
14,14.
16,64. 150 . 4798

01004, , . « » , 4